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PATENT  
Attorney's Docket No. 3521.182

ART UNIT: 2813

EXAMINER:

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: )  
SOMIT TALWAR et al. )  
Serial No.: 10/762,861 )  
Filed: January 22, 2004 )

For: **LASER THERMAL ANNEALING OF LIGHTLY DOPED SILICON  
SUBSTRATES**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on June 3, 2005 by Allston L. Jones (Reg. No. 27,906).

Signed: \_\_\_\_\_

**TRANSMITTAL OF INFORMATION DISCLOSURE STATEMENT WITHIN THREE  
MONTHS OF FILING OR BEFORE MAILING OF FIRST OFFICE ACTION  
(37 CFR 1.97(b))**

The information disclosure statement submitted herewith is being filed before the mailing date of a first Office action on the merits. 37 CFR 1.97(b).

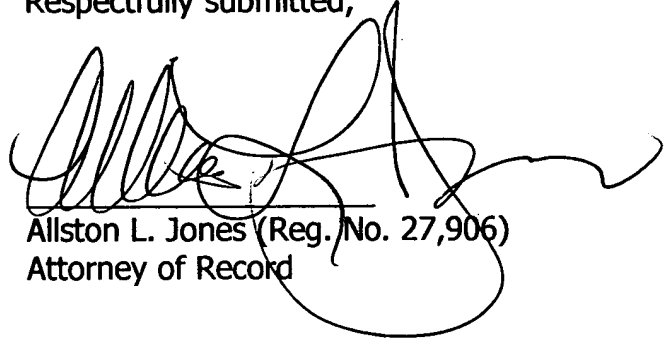
The citation listed on the attached PTO 1449, along with the enclosed copies of the references, provides the background and may be material to the examination of the above-identified application and is, therefore, submitted in compliance with the duty of disclosure in 37 C.F.R. 1.56, 1.97 and 1.98.

The Examiner is requested to make the citation of official record in this application.

This Information Disclosure Statement under 37 C.F.R. 1.56 and 1.97 is not to be construed as a representation that a search has been made, that additional information material to the examination of this application does not exist, or that any one or more of these citations constitutes prior art.

If fees are required with the filing of these documents, the Commissioner is authorized to charge such fees to Deposit Account No. 16-1331.

Respectfully submitted,

A handwritten signature in black ink, appearing to be 'Allston L. Jones', written over a horizontal line.

Allston L. Jones (Reg. No. 27,906)  
Attorney of Record

Date: June 3, 2005

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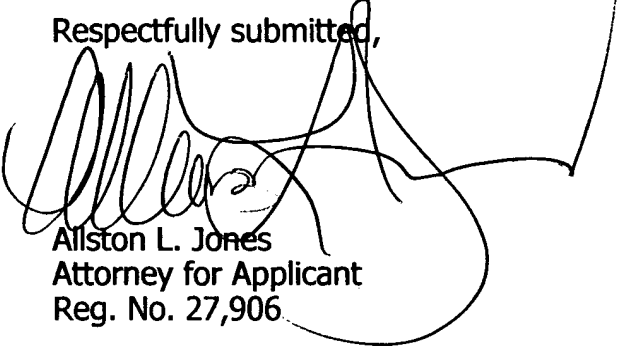
TRANSMITTAL LETTER

Transmitted herewith are the following documents:

1. Transmittal Letter in duplicate;
2. Transmittal of Information Disclosure Statement;
3. PTO-1449 form;
4. Copies of 2 non-patent references as listed on 1449 form; and
5. Postcard.

If any additional fees are required with the filing of these documents, the Commissioner is authorized to charge such fees or to credit any overpayment to Deposit Account No. 16-1331.

Respectfully submitted,



Allston L. Jones  
Attorney for Applicant  
Reg. No. 27,906

Date: June 3, 2005

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Attorney Docket No. 3521.182 (ALJ)

**FOR PTO-1449 (Modified)**  
**LIST OF PATENTS AND PUBLICATIONS FOR**  
**APPLICANTS INFORMATION DISCLOSURE**  
**STATEMENT**

(Use several sheets if necessary)

**ATTY. DOCKET NO.**

3521.182

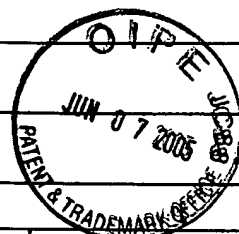
**SERIAL NO.**

10/762,861

**APPLICANT**  
 SOMIT TALWAR, et al.

**FILING DATE**  
 January 22, 2004

**GROUP**  
 2813



**REFERENCE DESIGNATION U.S. PATENT DOCUMENTS**

EXAMINER INITIAL		DOCUMENT NUMBER							DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	A	4	3	5	6	3	7	5	10-26-82	Josephy, et al.	219	121 LH	
	B	4	7	3	4	9	1	2	3-29-88	Scerbak, et al.	372	27	
	C	4	7	6	1	7	8	6	8-2-88	Baer	372	10	
	D	4	9	0	8	4	9	3	3-13-90	Susemihl	219	121.67	
	E	5	0	5	7	6	6	4	10-15-91	Johnson, et al.	219	121.69	
	F	6	2	0	8	6	7	3	3-27-01	Miyake	372	22	
	G	6	3	6	6	3	0	8	4-2-02	Hawryluk, et al.	347	256	
	H	6	7	4	7	2	4	5	6-8-04	Talwar, et al.	219	121.8	

**FOREIGN PATENT DOCUMENTS**

		DOCUMENT NUMBER							DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
													YES	NO

**OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)**

	I	Naem, Boothroyd, Calder, <i>CW Laser Annealed Small-Geometry NMOS Transistors</i> , Mat. Res. Soc. Symp. Proc. Vol. 23 (1984) pp 229-234.
	J	Goetzlich, Tsien, Ryssel, <i>Relaxation Behavior of Metastable AS and P Concentrations in SI After Pulsed and CW Laser Annealing</i> , Mat. Res. Soc. Symp. Proc. Vol. 23 (1984) pp 235-240

**EXAMINER**

**DATE CONSIDERED**

**EXAMINER:** Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.